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WHAT IS CLAIMED IS:

- 1. A metallic mirror comprising a substrate made of aluminum or an aluminum alloy, and an intermediate layer formed of ${\rm TiO}_2$ and a metallic reflective layer formed of ${\rm Cu}$ which are superposed on the substrate in order.
- The metallic mirror according to claim 1, which further comprises one or more protective layers provided on said metallic reflective layer.
- 3. The metallic mirror according to claim 1, which has a surface reflectance of 95% or higher.
- The metallic mirror according to claim 1, which is a metallic rotary polygonal mirror.
- The metallic mirror according to claim 2, wherein said protective layer is an aluminum oxide
 layer.
 - A metallic rotary polygonal mirror comprising;
 a metallic polygonal mirror substrate made of aluminum or an aluminum alloy;
 - an intermediate layer of ${\rm TiO_2}$ formed by vacuum deposition on the substrate;
 - a metallic reflective layer of Cu formed by vacuum

deposition on the intermediate layer; and

a protective layer including at least a layer of ${\rm Al}_2{\rm O}_3$, formed by vacuum deposition on the metallic reflective layer.

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 The metallic rotary polygonal mirror according to claim 6, wherein;

said intermediate layer has a layer thickness of from 50 nm to 150 nm, and said metallic reflective layer has a layer thickness of from 80 nm to 150 nm.

 The metallic rotary polygonal mirror according to claim 6, wherein;

said protective layer comprises a double layer consisting of a first protective layer and a second protective layer.

9. The metallic rotary polygonal mirror according to claim 8, wherein;

said first protective layer is a layer of ${\rm Al}_2{\rm O}_3,$ and said second protective layer is a layer of ${\rm SiO}_2.$

10. The metallic rotary polygonal mirror according to claim 9, wherein;

said first protective layer has a layer thickness of from 150 nm to 200 nm, and said second protective layer has a layer thickness of from 10 nm to 20 nm.

11. The metallic rotary polygonal mirror according to claim 6, wherein;

said protective layer comprises a triple layer consisting of a first protective layer, a second protective layer and a third protective layer.

12. The metallic rotary polygonal mirror according to claim 11, wherein;

said first protective layer is a layer of Al_2O_3 , said second protective layer is a layer of TiO_2 , and said third protective layer is a layer of SiO_2 .

13. The metallic rotary polygonal mirror according to claim 12, wherein;

said first protective layer has a layer thickness of from 150 nm to 200 nm, said second protective layer has a layer thickness of from 80 nm to 100 nm, and said third protective layer has a layer thickness of from 10 nm to 20 nm.

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- 14. The metallic rotary polygonal mirror according to claim 6, which has a surface reflectance of 95% or higher.
- 15. A process for producing a metallic rotary polygonal mirror, comprising the steps of;

forming an intermediate layer of TiO2 by vacuum

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deposition on a metallic polygonal mirror substrate metal comprised of aluminum or an aluminum alloy;

forming a high-reflectance metallic reflective layer of Cu by vacuum deposition on the intermediate layer; and

forming a protective layer including at least a layer of $\mathrm{Al}_2\mathrm{O}_3$, by vacuum deposition on the metallic reflective layer.

16. The process for producing a metallic rotary polygonal mirror according to claim 15, wherein;

during the formation of said intermediate layer of TiO2, O2 gas is added under a pressure of from 6.65 \times 10^{-3} Pa to 26.6 \times 10^{-3} Pa.

17. The process for producing a metallic rotary polygonal mirror according to claim 15, wherein;

during the formation of said high-reflectance metallic reflective layer of Cu, the metallic reflective layer is formed after the inside of a vacuum deposition chamber reaches a degree of vacuum of 2.66×10^{-3} Pa or above subsequently to the formation of said intermediate layer of TiO, film.

18. The process for producing a metallic rotary polygonal mirror according to claim 15, wherein; in the formation of said protective layer

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including at least a layer of Al_2O_3 , when the layer of Al_2O_3 is formed on said high-reflectance metallic thin film of Cu, the protective layer is formed without addition of any O_2 gas at the initial stage of film formation until the film comes to have a layer thickness of 15 to 30% of a stated layer thickness, and further thereon, after the film has been formed beyond 15 to 30% and until it comes to have the stated layer thickness, with addition of O_2 gas under a pressure of from 6.65×10^{-3} Pa to 26.6×10^{-3} Pa.

19. The process for producing a metallic rotary polygonal mirror according to claim 15, wherein;

said intermediate layer is formed in a layer thickness of from 50 nm to 150 nm, and said metallic reflective layer is formed in a layer thickness of from 80 nm to 150 nm.

20. The process for producing a metallic rotary polygonal mirror according to claim 15, wherein;

said protective layer is formed in a double layer consisting of a first protective layer and a second protective layer.

21. The process for producing a metallic rotary polygonal mirror according to claim 20, wherein; said first protective layer is a layer of Al₂O₃,

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and said second protective layer is a layer of SiO2.

22. The process for producing a metallic rotary polygonal mirror according to claim 21, wherein;

said first protective layer is formed in a layer thickness of from 150 nm to 200 nm, and said second protective layer is formed in a layer thickness of from 10 nm to 20 nm.

23. The process for producing a metallic rotary polygonal mirror according to claim 15, wherein;

said protective layer is formed in a triple layer consisting of a first protective layer, a second protective layer and a third protective layer.

24. The process for producing a metallic rotary polygonal mirror according to claim 23, wherein; said first protective layer is a layer of $\mathrm{Al}_2\mathrm{O}_3$, said second protective layer is a layer of TiO_2 , and said third protective layer is a layer of SiO_2 .

25. The process for producing a metallic rotary polygonal mirror according to claim 24, wherein;

said first protective layer is formed in a layer thickness of from 150 nm to 200 nm, said second protective layer is formed in a layer thickness of from 80 nm to 100 nm, and said third protective layer is

formed in a layer thickness of from 10 nm to 20 nm.

26. The process for producing a metallic rotary polygonal mirror according to claim 15, wherein;

said metallic rotary polygonal mirror has a surface reflectance of 95% or higher.